10/760,497, 7/25/05, 99A; CA-structure search

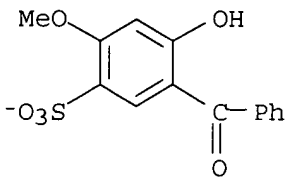
L17 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:246983 CAPLUS
DN 140:294802
TI Image forming material
IN Iwato, Kaoru; Sorori, Tadahiro
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 94 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1400350	A2	20040324	EP 2003-20551	20030917
	EP 1400350	A3	20040414		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	JP 2004109320	A2	20040408	JP 2002-269900	20020917
	JP 2004126049	A2	20040422	JP 2002-287818	20020930
	US 2004067435	A1	20040408	US 2003-662534	20030916
PRAI	JP 2002-269900	A	20020917		
	JP 2002-287818	A	20020930		

OS MARPAT 140:294802
AB Image-forming materials (e.g., planog. **printing plate** precursors) comprising a support and an image forming layer which is laminated on the support are described in which the image-forming layer contains at least a water-insol. and alkali-soluble polymer compound and a compound (especially an onium salt) having a structure represented by the general formula X-M+ (X- = an anion containing ≥1 substituent having an alkali-dissociating proton; and M+ = a counter cation which is an atomic group having an absorption maximum at a wavelength in the 760-1200 nm range) and having an absorption maximum at a wavelength in the range 760-1200 nm. The materials may addnl. include a light-heat converting agent.
IT **137309-11-6 675190-76-8 675190-85-9**
RL: TEM (Technical or engineered material use); USES (Uses)
(image forming materials containing salts and polymers)
RN 137309-11-6 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

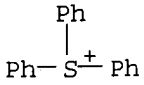
CM 1

CRN 65994-36-7
CMF C14 H11 O6 S



CM 2

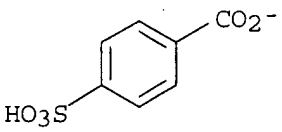
CRN 18393-55-0
CMF C18 H15 S



RN 675190-76-8 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

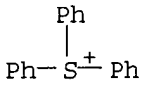
CM 1

CRN 96296-44-5
CMF C7 H5 O5 S



CM 2

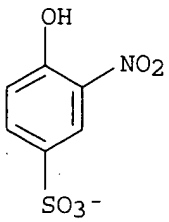
CRN 18393-55-0
CMF C18 H15 S



RN 675190-85-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-hydroxy-3-nitrobenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

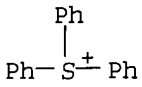
CM 1

CRN 154936-89-7
CMF C6 H4 N O6 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



=>

L19 ANSWER 1 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2005:467854 CAPLUS
DN 143:16503
TI **Photosensitive** composition containing specific sulfonic acid-generating compound for use in the **photosensitive** composition, and pattern forming method using the **photosensitive** composition
IN Wada, Kenji; Kodama, Kunihiko
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 133 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1536285	A2	20050601	EP 2004-27406	20041118
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR, IS, YU				
	JP 2005173549	A2	20050630	JP 2004-222931	20040730
	US 2005123859	A1	20050609	US 2004-993094	20041122
PRAI	JP 2003-392790	A	20031121		
	JP 2004-222931	A	20040730		

TI **Photosensitive** composition containing specific sulfonic acid-generating compound for use in the **photosensitive** composition, and pattern forming method using the **photosensitive** composition
AB Disclosed is a **photosensitive** composition comprising a compound capable of generating a specific sulfonic acid upon irradiation with actinic rays or a radiation; a. . . a specific sulfonic acid upon irradiation with an actinic ray or a radiation; and a pattern forming method using a **photosensitive** composition comprising a compound capable of generating a specific sulfonic acid upon irradiation with an actinic ray or a radiation.. . .
ST **photosensitive** compn sulfonate acid generating pattern **photoresist**
IT Photolithography
Photoresists
(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)
IT Acids, preparation
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(precursors; **photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)
IT 852572-36-2P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(delphotosensitive composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)
IT 112-53-8, 1-Dodecanol 313-50-8D, Perfluorobenzenesulfonic acid, methylpropanyl ester 3744-08-9, Triphenylsulfonium iodide 852572-07-7
RL: RCT (Reactant); RACT (Reactant or reagent)
(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)
IT 852572-09-9P 852572-11-3P 852572-13-5P 852572-15-7P 852572-17-9P
852572-19-1P 852572-21-5P 852572-23-7P 852572-25-9P

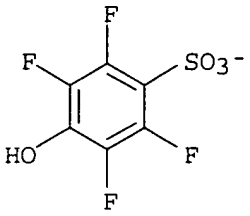
852572-27-1P 852572-29-3P 852572-31-7P 852572-33-9P 852572-34-0P
852572-35-1P 852572-37-3P 852572-38-4P 852572-39-5P 852572-41-9P
852572-42-0P 852572-44-2P 852572-46-4P 852572-47-5P 852572-48-6P
852572-49-7P 852572-52-2P 852572-54-4P 852572-56-6P 852572-58-8P
852572-60-2P 852572-62-4P 852572-64-6P 852572-66-8P 852572-68-0P
852572-69-1P 852572-70-4P 852572-71-5P 852572-72-6P 852572-73-7P
852572-74-8P 852572-76-0P 852572-77-1P 852572-78-2P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

IT **852572-19-1P**
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

RN 852572-19-1 CAPLUS
CN Sulfonium, triphenyl-, salt with 2,3,5,6-tetrafluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

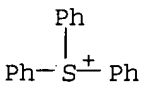
CM 1

CRN 852572-18-0
CMF C6 H F4 O4 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 2 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2005:256554 CAPLUS
DN 142:345143
TI Negative-working photopolymerizable photoimaging composition containing specific polymerization initiator for **image** recording materials
IN Shimada, Kazuto
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 92 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2005077984	A2	20050324	JP 2003-311254	20030903
PRAI	JP 2003-311254		20030903		

TI Negative-working photopolymerizable photoimaging composition containing specific polymerization initiator for **image** recording materials

ST neg photopolymerizable photoimaging compn **image** recording radical polymn initiator

IT Photoimaging materials
(photopolymerizable; neg.-working photopolymerizable photoimaging composition for **image** recording materials)

IT Polymerization catalysts
(radical; neg.-working photopolymerizable photoimaging composition for **image** recording materials)

IT 709037-32-1 790622-95-6 848421-84-1 848421-85-2 **848421-86-3** **848421-87-4** **848421-89-6** 848421-90-9 848421-91-0 848421-92-1 **848440-63-1**
RL: CAT (Catalyst use); USES (Uses)
(radical polymerization initiator)

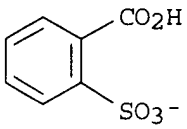
IT **848421-86-3** **848421-87-4** **848421-89-6** **848440-63-1**
RL: CAT (Catalyst use); USES (Uses)
(radical polymerization initiator)

RN 848421-86-3 CAPLUS

CN Sulfonium, triphenyl-, salt with 2-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

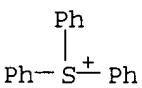
CM 1

CRN 58592-21-5
CMF C7 H5 O5 S



CM 2

CRN 18393-55-0
CMF C18 H15 S

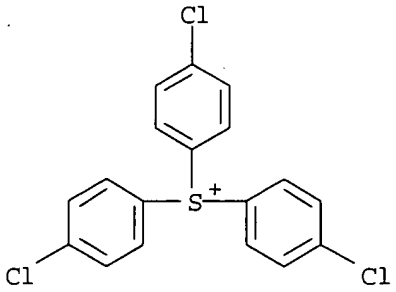


RN 848421-87-4 CAPLUS

CN Sulfonium, tris(4-chlorophenyl)-, salt with 4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

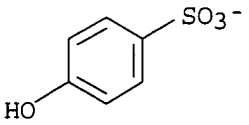
CM 1

CRN 125853-07-8
CMF C18 H12 Cl3 S



CM 2

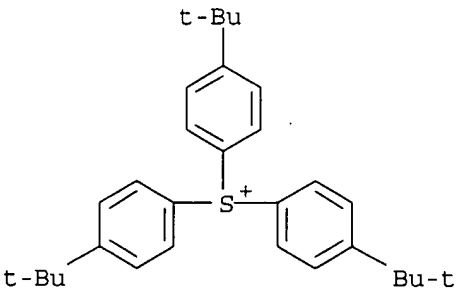
CRN 45935-73-7
CMF C6 H5 O4 S



RN 848421-89-6 CAPLUS
CN Sulfonium, tris[4-(1,1-dimethylethyl)phenyl]-, salt with 2-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

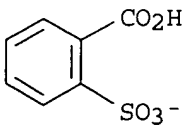
CM 1

CRN 91815-56-4
CMF C30 H39 S



CM 2

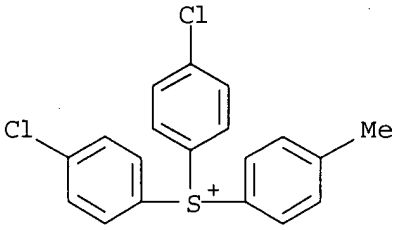
CRN 58592-21-5
CMF C7 H5 O5 S



RN 848440-63-1 CAPLUS
CN Sulfonium, bis(4-chlorophenyl)(4-methylphenyl)-, salt with 5-sulfo-1,3-benzenedicarboxylic acid (1:1) (9CI) (CA INDEX NAME)

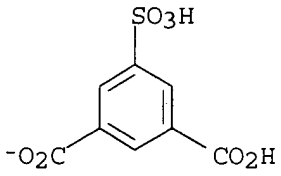
CM 1

CRN 667888-57-5
CMF C19 H15 Cl2 S



CM 2

CRN 65086-74-0
CMF C8 H5 O7 S



L19 ANSWER 3 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:963502 CAPLUS
DN 141:417925
TI Positive-working vacuum-UV **photoresist** composition and patterning method using the same
IN Sasaki, Tomoya
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 99 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004318046	A2	20041111	JP 2003-293188	20030813
PRAI	JP 2003-94329	A	20030331		

TI Positive-working vacuum-UV **photoresist** composition and patterning method using the same
AB Disclosed is the pos.-working vacuum-UV **photoresist** composition especially suited for a F2 excimer laser (157 nm) comprising (a) a resin having a repeating unit FR0C-CFR1, FR0C-CF(OR2),. . .
ST pos working vacuum UV **photoresist** compn patterning photolithog
IT Photolithography
Photoresists
(pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)
IT 66003-78-9 144317-44-2 **756532-52-2**
RL: TEM (Technical or engineered material use); USES (Uses)
(photoacid; pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

IT 791849-04-2P
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

IT 791848-97-0 791848-99-2 791849-01-9 791849-07-5 791849-10-0
791849-12-2 791849-14-4 791849-15-5 791849-17-7 791853-95-7
791853-96-8 791853-98-0 791854-01-8 791854-03-0
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

IT 699-95-6
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of resin for pos.-working vacuum-UV **photoresist** composition)

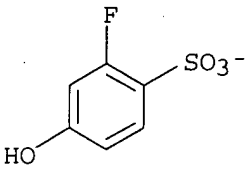
IT 142507-56-0P 791849-03-1P 791849-18-8P 791849-19-9P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation of resin for pos.-working vacuum-UV **photoresist** composition)

IT **756532-52-2**
RL: TEM (Technical or engineered material use); USES (Uses)
(photoacid; pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

RN 756532-52-2 CAPLUS
CN Sulfonium, triphenyl-, salt with 2-fluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

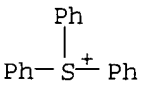
CM 1

CRN 756532-51-1
CMF C6 H4 F O4 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 4 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:960408 CAPLUS
DN 141:417914
TI Positive-working vacuum-UV **photoresist** composition and patterning method using the same
IN Sasaki, Tomoya
PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 113 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2004318045	A2	20041111	JP 2003-293175	20030813
PRAI JP 2003-96391	A	20030331		

TI Positive-working vacuum-UV **photoresist** composition and patterning method using the same

AB Disclosed is the pos.-working vacuum-UV **photoresist** composition comprising (a) a resin having a repeating unit -C(OY){-CR50R51R52}{-CR53R54R55} (R50-55 = H, F, alkyl; and Y = H, organic. . .

ST pos working resist **photoresist** compn patterning photolithog; vacuum UV **photoresist**

IT Photolithography
(pos.-working vacuum-UV **photoresist** composition containing resins and photoacid)

IT Photoresists
(vacuum-UV; pos.-working vacuum-UV **photoresist** composition containing resins and photoacid)

IT 66003-78-9 144317-44-2 **756532-52-2**
RL: TEM (Technical or engineered material use); USES (Uses)
(photoacid; pos.-working vacuum-UV **photoresist** composition from)

IT 262617-10-7P, tert-Butyl acrylate-norbornene-tetrafluoroethylene copolymer 792284-28-7P
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos.-working vacuum-UV **photoresist** composition from)

IT 105935-25-9 357397-06-9 365568-64-5 622378-55-6 680603-11-6
792285-90-6 792286-10-3 792286-34-1 792286-57-8 792286-72-7
792286-88-5 792287-05-9 792287-44-6 792916-51-9 792916-53-1
792916-55-3
RL: TEM (Technical or engineered material use); USES (Uses)
(pos.-working vacuum-UV **photoresist** composition from)

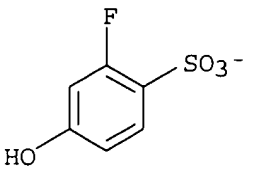
IT **756532-52-2**
RL: TEM (Technical or engineered material use); USES (Uses)
(photoacid; pos.-working vacuum-UV **photoresist** composition from)

RN 756532-52-2 CAPLUS

CN Sulfonium, triphenyl-, salt with 2-fluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

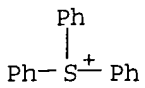
CM 1

CRN 756532-51-1
CMF C6 H4 F O4 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



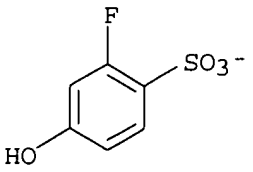
L19 ANSWER 5 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:753223 CAPLUS
DN 141:268557
TI Positive resist composition and method of forming a resist pattern using the same
IN Sasaki, Tomoya
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 80 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1457819	A2	20040915	EP 2004-4961	20040303
	EP 1457819	A3	20050622		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK				
	JP 2004279471	A2	20041007	JP 2003-67010	20030312
PRAI	JP 2003-67010	A	20030312		

AB A pos. **photoresist** composition comprises (A) a resin comprising specific repeating units and coming to have enhanced solubility in an alkaline developing solution. . .
ST pos **photoresist** compn pattern
IT Positive photoresists
(pos. **photoresist** composition for forming resist pattern)
IT 66003-78-9 144317-44-2 205682-99-1 365971-61-5 365971-70-6
756532-52-2 756532-53-3
RL: TEM (Technical or engineered material use); USES (Uses)
(acid generator; pos. **photoresist** composition for forming resist pattern)
IT 756532-32-8P 756532-34-0P 756532-37-3P 756532-38-4P 756532-39-5P
756532-40-8P 756532-41-9P 756532-42-0P 756532-44-2P 756532-45-3P
756532-47-5P 756532-48-6P 756532-50-0P
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos. **photoresist** composition for forming resist pattern)
IT 75-07-0, Acetaldehyde, reactions 107-30-2, Chloromethyl methyl ether 802-93-7, 1,3-Bis(2-hydroxyhexafluoroisopropyl)benzene 1826-67-1, Vinylmagnesium bromide
RL: RCT (Reactant); RACT (Reactant or reagent)
(pos. **photoresist** composition for forming resist pattern)
IT 501935-24-6P 585573-34-8P 585573-35-9P 585573-59-7P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(pos. **photoresist** composition for forming resist pattern)
IT **756532-52-2**
RL: TEM (Technical or engineered material use); USES (Uses)
(acid generator; pos. **photoresist** composition for forming resist pattern)
RN 756532-52-2 CAPLUS
CN Sulfonium, triphenyl-, salt with 2-fluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

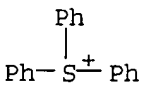
CM 1

CRN 756532-51-1
CMF C6 H4 F O4 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 6 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:633141 CAPLUS
DN 141:181996
TI **Image** forming material
IN Iwato, Kaoru
PA Fuji Photo Film Co., Ltd., Japan
SO U.S. Pat. Appl. Publ., 67 pp.
CODEN: USXXCO
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2004152012	A1	20040805	US 2004-760497	20040121
	JP 2004226794	A2	20040812	JP 2003-15905	20030124
	JP 2004233854	A2	20040819	JP 2003-24499	20030131
PRAI	JP 2003-15905	A	20030124		
	JP 2003-24499	A	20030131		

OS MARPAT 141:181996
TI **Image** forming material
AB The present invention relates to an **image** forming material having, on a substrate, an **image** forming layer that includes at least (A) a novolac type phenolic resin containing phenol as a structural unit, (B) a. . .
ST pos planog printing plate **image** material
IT Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(novolak; pos. planog. printing plate **image** forming material containing)
IT Printing plates
(planog.; pos. planog. printing plate **image** forming material)
IT 445497-24-5 733046-76-9 733046-78-1 733046-80-5 733046-82-7
733046-84-9 733046-85-0 733046-87-2
RL: TEM (Technical or engineered material use); USES (Uses)
(ammonium compound; pos. planog. printing plate **image** forming material containing)
IT 121438-28-6 504387-13-7 **675190-76-8** 675190-77-9
675190-84-8 675190-90-6 675190-91-7 675190-93-9 675190-98-4

675190-99-5 675191-00-1 675191-03-4 675588-03-1 675588-04-2
RL: TEM (Technical or engineered material use); USES (Uses)
(onium salt; pos. planog. printing plate **image** forming material containing)

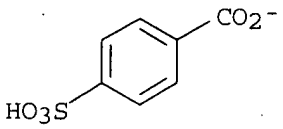
IT 35464-74-5, m-Cresol-p-cresol-formaldehyde-phenol copolymer 56700-20-0, Formaldehyde-phenol-2,5-xylenol copolymer
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(pos. planog. printing plate **image** forming material containing)

IT **675190-76-8**
RL: TEM (Technical or engineered material use); USES (Uses)
(onium salt; pos. planog. printing plate **image** forming material containing)

RN 675190-76-8 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

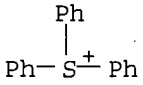
CM 1

CRN 96296-44-5
CMF C7 H5 O5 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



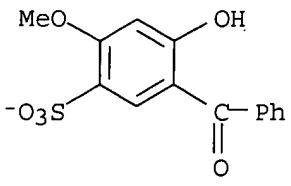
L19 ANSWER 7 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:246983 CAPLUS
DN 140:294802
TI **Image** forming material
IN Iwato, Kaoru; Sorori, Tadahiro
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 94 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 1400350	A2	20040324	EP 2003-20551	20030917
EP 1400350	A3	20040414		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
JP 2004109320	A2	20040408	JP 2002-269900	20020917
JP 2004126049	A2	20040422	JP 2002-287818	20020930
US 2004067435	A1	20040408	US 2003-662534	20030916

PRAI JP 2002-269900 A 20020917
JP 2002-287818 A 20020930
OS MARPAT 140:294802
TI **Image** forming material
AB **Image**-forming materials (e.g., planog. printing plate precursors) comprising a support and an **image** forming layer which is laminated on the support are described in which the **image**-forming layer contains at least a water-insol. and alkali-soluble polymer compound and a compound (especially an onium salt) having a structure. . . range) and having an absorption maximum at a wavelength in the range 760-1200 nm. The materials may addnl. include a light-**heat** converting agent.
ST planog printing plate precursor salt polymer; onium salt polymer **image** forming material
IT Fluoropolymers, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(**image** forming materials containing salts and polymers)
IT Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(novolak; **image** forming materials containing salts and polymers)
IT Printing plates
(planog.; **image** forming materials containing salts and polymers)
IT 56992-87-1P, N-(p-Aminosulfonylphenyl)methacrylamide
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(**image** forming materials containing salts and polymers)
IT 463312-06-3P, Acrylonitrile-N-(p-Aminosulfonylphenyl)methacrylamide-ethyl methacrylate-methyl methacrylate copolymer
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(**image** forming materials containing salts and polymers)
IT 118590-23-1 121438-28-6 **137309-11-6** 207793-00-8
216861-97-1 221388-40-5 221388-40-5 501332-52-1 504387-13-7
675190-76-8 675190-77-9 675190-78-0 675190-80-4
675190-82-6 675190-84-8 **675190-85-9** 675190-87-1
675190-90-6 675190-91-7 675190-92-8 675190-93-9 675190-95-1
675190-97-3 675190-98-4 675190-99-5 675191-00-1 675191-01-2
675191-02-3 675191-03-4 675191-04-5 675191-05-6 675191-06-7
675191-07-8 675191-08-9 675191-09-0 675191-10-3 675191-11-4
675191-12-5 675191-14-7 675191-15-8 675191-16-9 675191-17-0
675191-18-1 675191-19-2 675191-20-5 675588-03-1 675588-04-2
675588-05-3 675588-06-4 675588-07-5 675588-08-6
RL: TEM (Technical or engineered material use); USES (Uses)
(**image** forming materials containing salts and polymers)
IT **137309-11-6 675190-76-8 675190-85-9**
RL: TEM (Technical or engineered material use); USES (Uses)
(**image** forming materials containing salts and polymers)
RN 137309-11-6 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

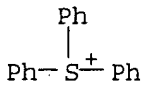
CM 1

CRN 65994-36-7
CMF C14 H11 O6 S



CM 2

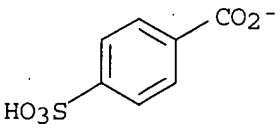
CRN 18393-55-0
CMF C18 H15 S



RN 675190-76-8 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

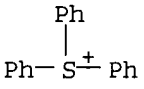
CM 1

CRN 96296-44-5
CMF C7 H5 O5 S



CM 2

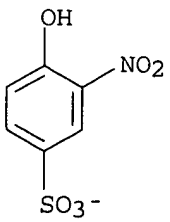
CRN 18393-55-0
CMF C18 H15 S



RN 675190-85-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-hydroxy-3-nitrobenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

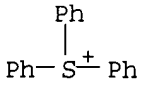
CM 1

CRN 154936-89-7
CMF C6 H4 N O6 S



CM 2

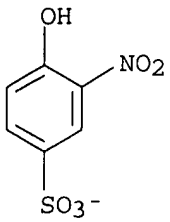
CRN 18393-55-0
CMF C18 H15 S



RN 675190-85-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-hydroxy-3-nitrobenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

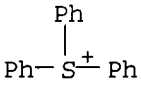
CM 1

CRN 154936-89-7
CMF C6 H4 N O6 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 8 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:750701 CAPLUS
DN 139:283396
TI Sulfonium salts for photoacid generators, their manufacture, **photosensitive** resin compositions containing them, and their argon laser-sensitive photoresists
IN Tarumoto, Naohiro; Yamaoka, Tsugio; Yoshikawa, Katsumasa; Yamazaki, Hajime
PA Hodogaya Chemical Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

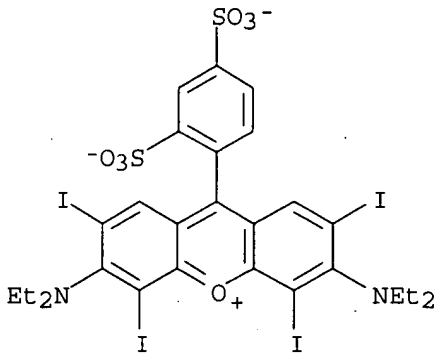
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003267968	A2	20030925	JP 2002-68269	20020313
PRAI	JP 2002-68269		20020313		

OS MARPAT 139:283396
TI Sulfonium salts for photoacid generators, their manufacture, **photosensitive** resin compositions containing them, and their argon laser-sensitive photoresists
ST sulfonium photoacid generator **photoresist** argon laser
IT **605655-38-7**
RL: CAT (Catalyst use); USES (Uses)
(photoacid generators; sulfonium salt photoacid generators for Ar laser-sensitive photoresists)
IT **605655-38-7**
RL: CAT (Catalyst use); USES (Uses)
(photoacid generators; sulfonium salt photoacid generators for Ar

laser-sensitive photoresists)
RN 605655-38-7 CAPLUS
CN Xanthylium, 3,6-bis(diethylamino)-9-(2,4-disulfophenyl)-2,4,5,7-tetraiodo-, inner salt, ion(1-), triphenylsulfonium (9CI) (CA INDEX NAME)

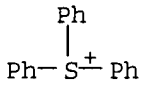
CM 1

CRN 605655-37-6
CMF C27 H25 I4 N2 O7 S2



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 9 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:750689 CAPLUS
DN 139:267987
TI Pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light, their preparation, and their positive **photosensitive** resin compositions and **photosensitive** materials
IN Tarumoto, Naohiro; Yamaoka, Tsugio; Yoshikawa, Katsumasa; Yamazaki, Hajime
PA Hodogaya Chemical Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003267949	A2	20030925	JP 2002-67267	20020312
PRAI	JP 2002-67267		20020312		

OS MARPAT 139:267987
TI Pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light, their preparation, and their positive **photosensitive** resin compositions and **photosensitive** materials
ST pyrenesulfonic acid onium salt photoacid generator pos **photoresist** ; photoacid generator i line sensitive .
IT Positive photoresists

(i-line; preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT Onium compounds
Sulfonic acids, uses
RL: CAT (Catalyst use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT 158593-28-3 603117-24-4 **603117-27-7 603117-29-9**
RL: CAT (Catalyst use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT 1483-72-3, Diphenyliodonium chloride 6358-69-6, Pyranine
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

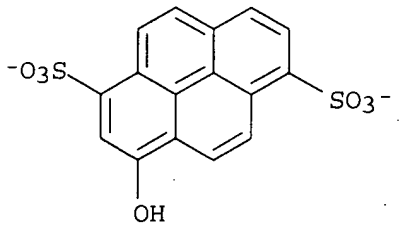
IT 129674-22-2, p-(tert-Butyloxycarbonyloxy)styrene-p-hydroxystyrene copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT **603117-27-7 603117-29-9**
RL: CAT (Catalyst use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

RN 603117-27-7 CAPLUS
CN Sulfonium, triphenyl-, salt with 3-hydroxy-1,6-pyrenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

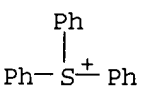
CM 1

CRN 603117-26-6
CMF C16 H8 O7 S2



CM 2

CRN 18393-55-0
CMF C18 H15 S

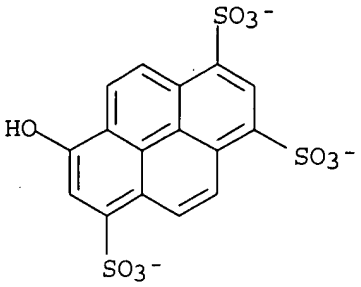


RN 603117-29-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 8-hydroxy-1,3,6-pyrenetrisulfonic acid (3:1) (9CI) (CA INDEX NAME)

CM 1

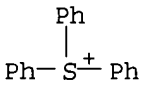
CRN 57206-23-2

CMF C16 H7 O10 S3



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 10 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2002:707555 CAPLUS
DN 137:255361
TI **Heat**-mode negative-working lithographic printing master plate containing onium salt polymerization initiator
IN Shimada, Kazuto; Sorori, Tadahiro
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 34 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002268217	A2	20020918	JP 2001-69168	20010312
	US 2003017411	A1	20030123	US 2002-93746	20020311
	US 6623910	B2	20030923		
PRAI	JP 2001-69168	A	20010312		

TI **Heat**-mode negative-working lithographic printing master plate containing onium salt polymerization initiator
AB The **heat**-mode neg.-working lithog. printing master plate comprises an IR-laser recordable **photosensitive** layer on a support which contains (a) a light-to-**heat** conversion agent, (b) a compound having a polymerizable unsatd. group, and (c) an onium salt having a polyvalent counter ion. . . . anion increased an electron d. of the counter anion, resulting in promoting a decomposition of the onium salt upon receiving **heat**.
ST onium salt polymn initiator lithog printing master plate; **heat** mode neg working lithog printing master plate; diazonium iodonium sulfonium salt polymn initiator
IT Lithographic plates
Polymerization catalysts
(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)
IT Onium compounds

Sulfonium compounds
RL: CAT (Catalyst use); USES (Uses)
(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT Polyurethanes, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT Onium compounds
RL: CAT (Catalyst use); USES (Uses)
(iodonium; **heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT 57592-66-2, Pentaerythritol tetraacrylate homopolymer 139385-71-0, Glycerin dimethacrylate-hexamethylenediisocyanate copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT 183745-01-9 460337-33-1 460337-34-2
RL: TEM (Technical or engineered material use); USES (Uses)
(light-to-**heat** conversion agent; **heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT 460337-35-3 460337-36-4 460337-37-5 **460337-38-6** 460337-39-7 460337-41-1 460337-42-2 460337-43-3 460337-44-4 460337-46-6 460337-47-7 460337-48-8
RL: CAT (Catalyst use); USES (Uses)
(polymerization initiator; **heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

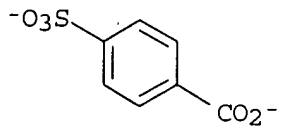
IT **460337-38-6**
RL: CAT (Catalyst use); USES (Uses)
(polymerization initiator; **heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

RN 460337-38-6 CAPLUS

CN Sulfonium, bis(4-chlorophenyl)phenyl-, salt with 4-sulfobenzoic acid (2:1) (9CI) (CA INDEX NAME)

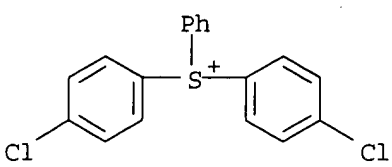
CM 1

CRN 161664-30-8
CMF C7 H4 O5 S



CM 2

CRN 127855-17-8
CMF C18 H13 Cl2 S



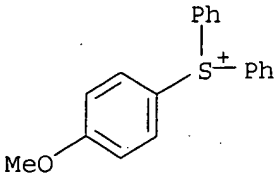
L19 ANSWER 11 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2001:261336 CAPLUS
DN 134:303007
TI Positive-working 220 nm light-sensitive chemically amplified **photoresist** composition containing specific acid generator
IN Kodama, Kunihiko; Sato, Kenichiro; Aogo, Toshiaki
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 51 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001100402	A2	20010413	JP 1999-273160	19990927
	US 6410204	B1	20020625	US 2000-669907	20000927
PRAI	JP 1999-273160	A	19990927		

TI Positive-working 220 nm light-sensitive chemically amplified **photoresist** composition containing specific acid generator
ST pos working light sensitive amplified **photoresist** compn photoacid generator
IT Positive photoresists
Semiconductor device fabrication
(pos.-working 220 nm light-sensitive **photoresist** composition)
IT 71-43-2, Benzene, reactions 85-47-2, 1-Naphthalenesulfonic acid 945-51-7, Diphenyl sulfoxide 2049-95-8, tert-Amylbenzene 4270-70-6, Triphenylsulfonium chloride 7758-05-6, Potassium iodate 12027-06-4, Ammonium iodide
RL: RCT (Reactant); RACT (Reactant or reagent)
(photoacid generator in pos.-working chemical amplified **photoresist** composition)
IT 3744-08-9P, Triphenylsulfonium iodide 249300-51-4DP, Iodonium,bis[4-(1,1-dimethylpropyl)phenyl]-, salt with sulfate
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(photoacid generator in pos.-working chemical amplified **photoresist** composition)
IT 13612-82-3P 14721-86-9P 137309-38-7P 137309-39-8P 220155-99-7P **334541-40-1P** 334541-43-4P **334541-46-7P** 334541-49-0P 334541-52-5P 334541-54-7P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photoacid generator in pos.-working chemical amplified **photoresist** composition)
IT **334541-40-1P 334541-46-7P**
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photoacid generator in pos.-working chemical amplified **photoresist** composition)
RN 334541-40-1 CAPLUS
CN Sulfonium, (4-methoxyphenyl)diphenyl-, salt with 6,7-dihydroxy-2-naphthalenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

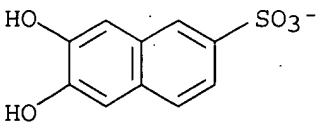
CM 1

CRN 70084-23-0
CMF C19 H17 O S



CM 2

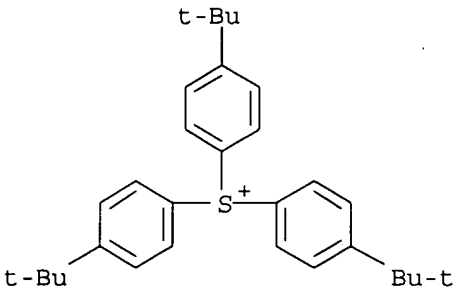
CRN 32743-86-5
CMF C10 H7 O5 S



RN 334541-46-7 CAPLUS
CN Sulfonium, tris[4-(1,1-dimethylethyl)phenyl]-, salt with 6,7-dihydroxy-2-naphthalenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

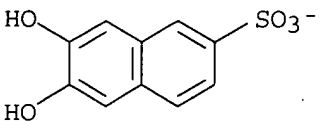
CM 1

CRN 91815-56-4
CMF C30 H39 S



CM 2

CRN 32743-86-5
CMF C10 H7 O5 S



L19 ANSWER 12 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1998:106203 CAPLUS
DN 128:198666
TI Negative-working presensitized lithographic plate useful for direct platemaking
IN Kobayashi, Fumikazu

PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 33 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10039509	A2	19980213	JP 1996-192517	19960722
	JP 3645362	B2	20050511		
	US 5965319	A	19991012	US 1997-891834	19970714
PRAI	JP 1996-192517	A	19960722		

AB . . . of platemaking directly from digital data using IR lasers and shows good storage stability, broader latitude in the condition of **heat** treatment after exposure, and high printing durability.

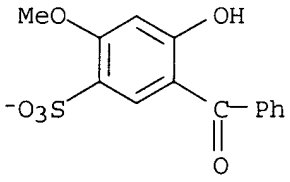
IT 87263-95-4P 137308-86-2P 137309-10-5P **137309-11-6P**
161679-94-3P 166658-57-7P
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(presensitized lithog. plate containing onium sulfonate, crosslinking agent, alkali-soluble resin, and IR absorbent)

IT **137309-11-6P**
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(presensitized lithog. plate containing onium sulfonate, crosslinking agent, alkali-soluble resin, and IR absorbent)

RN 137309-11-6 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

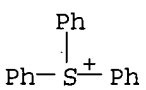
CM 1

CRN 65994-36-7
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 13 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1997:765308 CAPLUS
DN 128:108451
TI Sulfonium or iodonium disulfonates and positive-working **photosensitive** composition containing them
IN Aogo, Toshiaki; Sato, Kenichiro; Kodama, Kunihiko

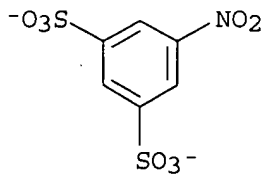
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 58 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09309874	A2	19971202	JP 1996-125949	19960521
PRAI	JP 1996-125949		19960521		

OS MARPAT 128:108451
TI Sulfonium or iodonium disulfonates and positive-working **photosensitive** composition containing them
AB . . . or II (R4-5 have the same definition as R1-3; Ar has the same definition as above) are claimed. The pos.-working **photosensitive** composition, useful for lithog. plate making, elec. circuit boards, etc., contains a resin having groups which are decomposed upon acids. . .
ST pos **photoresist** sulfonium iodonium photoacid generator; disulfonate sulfonium iodonium photoacid generator **photoresist**; resist photo sulfonium disulfonate photoacid generator
IT Positive photoresists
(preparation of sulfonium or iodonium disulfonates as photoacid generators for pos.-working **photosensitive** composition)
IT **201156-46-9P 201156-50-5P 201156-52-7P**
201156-54-9P 201156-55-0P 201156-57-2P 201156-58-3P
201156-60-7P 201156-61-8P 201302-74-1P 201302-77-4P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(preparation of sulfonium or iodonium disulfonates as photoacid generators for pos.-working **photosensitive** composition)
IT 1483-72-3, Diphenyliodonium chloride 3709-43-1, 4,4'-Dinitrostilbene-2,2'-disulfonic acid disodium salt 4270-70-6, Triphenylsulfonium chloride 5421-53-4, 4,4'-Bis(tert-butylphenyl)iodonium chloride 27154-83-2 69031-60-3 201156-40-3 201156-41-4 201156-43-6
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of sulfonium or iodonium disulfonates as photoacid generators for pos.-working **photosensitive** composition)
IT **201156-63-0 201156-65-2 201156-66-3**
201156-69-6 201156-71-0 201156-72-1 201302-80-9 201363-44-2
RL: TEM (Technical or engineered material use); USES (Uses)
(preparation of sulfonium or iodonium disulfonates as photoacid generators for pos.-working **photosensitive** composition)
IT **201156-46-9P 201156-50-5P 201156-52-7P**
201156-54-9P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(preparation of sulfonium or iodonium disulfonates as photoacid generators for pos.-working **photosensitive** composition)
RN 201156-46-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-nitro-1,3-benzenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

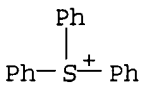
CM 1

CRN 201156-45-8
CMF C6 H3 N O8 S2



CM 2

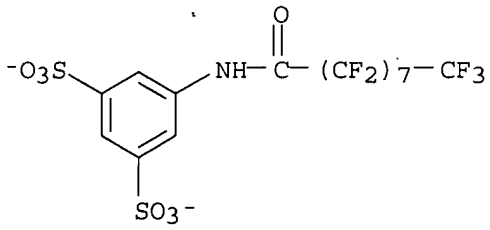
CRN 18393-55-0
CMF C18 H15 S



RN 201156-50-5 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-[(2,2,3,3,4,4,5,5,6,6,7,7,8,8,9,9,9-heptadecafluoro-1-oxononyl)amino]-1,3-benzenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

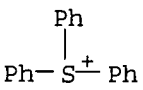
CM 1

CRN 201156-49-2
CMF C15 H4 F17 N O7 S2



CM 2

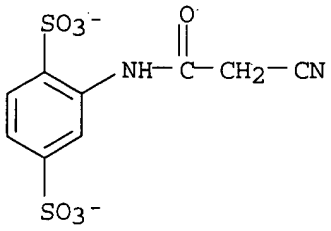
CRN 18393-55-0
CMF C18 H15 S



RN 201156-52-7 CAPLUS
CN Sulfonium, triphenyl-, salt with 2-[(cyanoacetyl)amino]-1,4-benzenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

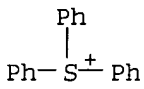
CM 1

CRN 201156-51-6
CMF C9 H6 N2 O7 S2



CM 2

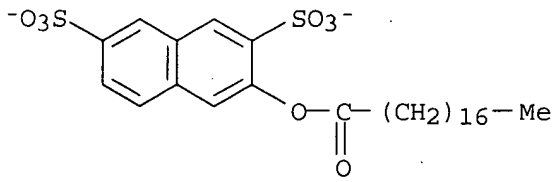
CRN 18393-55-0
CMF C18 H15 S



RN 201156-54-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 3,6-disulfo-2-naphthalenyl octadecanoate (2:1) (9CI) (CA INDEX NAME)

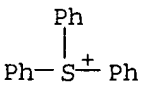
CM 1

CRN 201156-53-8
CMF C28 H40 O8 S2



CM 2

CRN 18393-55-0
CMF C18 H15 S

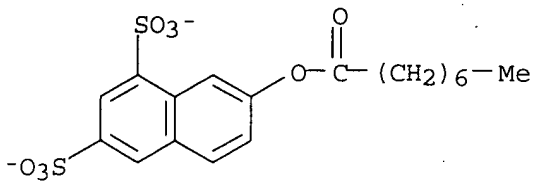


IT **201156-63-0 201156-65-2 201156-66-3**
RL: TEM (Technical or engineered material use); USES (Uses)
(preparation of sulfonium or iodonium disulfonates as photoacid generators for pos.-working **photosensitive** composition)
RN 201156-63-0 CAPLUS
CN Sulfonium, bis(4-hydroxyphenyl)phenyl-, salt with 6,8-disulfo-2-naphthalenyl octanoate (2:1) (9CI) (CA INDEX NAME)

CM 1

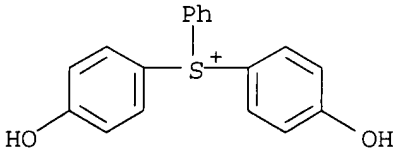
CRN 201156-62-9

CMF C18 H20 O8 S2



CM 2

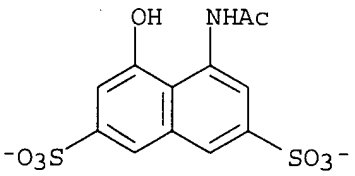
CRN 120397-56-0
CMF C18 H15 O2 S



RN 201156-65-2 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-(acetylamino)-5-hydroxy-2,7-naphthalenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

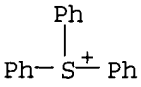
CM 1

CRN 201156-64-1
CMF C12 H9 N O8 S2



CM 2

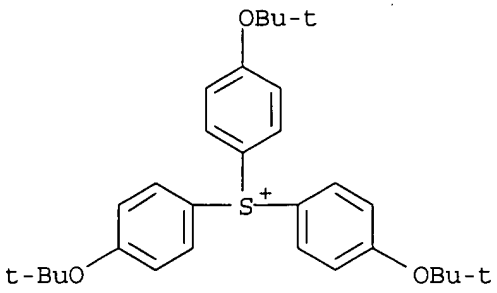
CRN 18393-55-0
CMF C18 H15 S



RN 201156-66-3 CAPLUS
CN Sulfonium, tris[4-(1,1-dimethylethoxy)phenyl]-, 2,6-naphthalenedisulfonate (2:1) (9CI) (CA INDEX NAME)

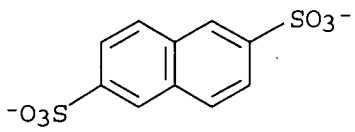
CM 1

CRN 137455-55-1
CMF C30 H39 O3 S



CM 2

CRN 55077-34-4
CMF C10 H6 O6 S2



L19 ANSWER 14 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1995:386319 CAPLUS
DN 122:136009
TI Washfast dyed polyester fabrics with improved color brightness and depth
IN Yamada, Setsuo; Kobayashi, Shigenobu
PA Teijin Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 06330463	A2	19941129	JP 1993-121438	19930524
PRAI JP 1993-121438		19930524		

AB The fabrics comprise polyester fibers dyed with dyes (e.g., cationic dyes) and have the surface coated with **heat**-curable vinyl polymers containing oxazoline groups in the side chain or derivs. thereof and have color yield value (ΔE; JIS Z-8730-1980). . . . spun, made into a woven fabric, dyed with a solution containing 2% (on fiber) C.I. Basic Blue 75, washed, dried, **heat** set, treated with an aqueous solution containing 10% C1-4 alkyl acrylate-styrene-vinyloxazoline copolymer to 50% pickup, dried, and **heat** treated 1 min at 170° to give a colored fabric with ΔE 12.4 initially and 12.6 after 5 washings.

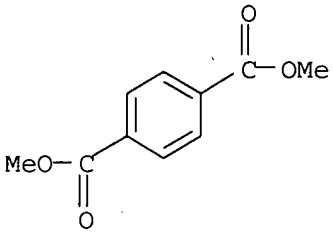
IT **161261-41-2**
RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(fiber; washfast dyed polyester fabrics with improved color brightness and depth)

IT **161261-41-2**
RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(fiber; washfast dyed polyester fabrics with improved color brightness and depth)

RN 161261-41-2 CAPLUS
CN Sulfonium, tributyl-, salt with 5-sulfo-1,3-benzenedicarboxylic acid (1:1), polymer with dimethyl 1,4-benzenedicarboxylate and 1,2-ethanediol (9CI) (CA INDEX NAME)

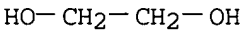
CM 1

CRN 120-61-6
CMF C10 H10 O4



CM 2

CRN 107-21-1
CMF C2 H6 O2

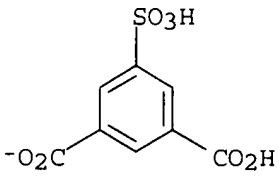


CM 3

CRN 161261-40-1
CMF C12 H27 S . C8 H5 O7 S

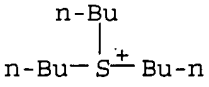
CM 4

CRN 65086-74-0
CMF C8 H5 O7 S



CM 5

CRN 39895-78-8
CMF C12 H27 S



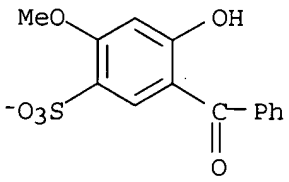
L19 ANSWER 15 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1994:120755 CAPLUS
DN 120:120755
TI **Photosensitive** composition for lithographic plates and **photoresist**
IN Uenishi, Kazuya; Umehara, Akira; Aotani, Norimasa; Yamaoka, Tsugio
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 05005993	A2	19930114	JP 1991-159093	19910628
PRAI JP 1991-159093		19910628		

TI **Photosensitive** composition for lithographic plates and **photoresist**
ST **photosensitive** compn **photoresist** lithog plate; onium arom sulfonate **photosensitive** compn
IT Lithographic plates
(manufacture of, **photosensitive** compns. for)
IT Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(novolak, **photoresist** compns. containing)
IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer 74508-34-2 87261-04-9 137308-83-9 137308-84-0 137309-03-6 137309-10-5 137337-64-5 151461-54-0
RL: USES (Uses)
(**photosensitive** composition containing)
IT 137308-86-2P, Diphenyliodonium 9,10-dimethoxyanthracene-2-sulfonate **137309-11-6P**
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, **photosensitive** composition containing)
IT **137309-11-6P**
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, **photosensitive** composition containing)
RN 137309-11-6 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

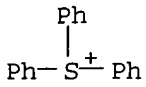
CM 1

CRN 65994-36-7
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



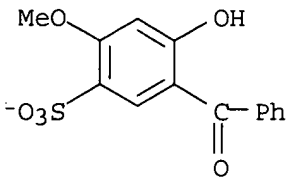
L19 ANSWER 16 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1993:505909 CAPLUS
DN 119:105909
TI **Photosensitive** compositions with high photosensitivity and resolution
IN Uenishi, Kazuya; Aotani, Norimasa; Umehara, Akira; Yamaoka, Tsugio
PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 05045878	A2	19930226	JP 1991-204205	19910814
PRAI JP 1991-204205		19910814		

OS MARPAT 119:105909
TI **Photosensitive** compositions with high photosensitivity and resolution
ST **photosensitive** compn onium arom sulfonate
IT 2203-14-7 3089-11-0, Hexamethoxymethylmelamine 24979-70-2, Poly(p-hydroxystyrene) 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer 137308-83-9 137308-92-0 137309-13-8
RL: USES (Uses)
(**photoresist** containing)
IT 137308-86-2P **137309-11-6P**
RL: PREP (Preparation)
(preparation of, **photoresist** containing)
IT **137309-11-6P**
RL: PREP (Preparation)
(preparation of, **photoresist** containing)
RN 137309-11-6 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 65994-36-7
CMF C14 H11 O6 S



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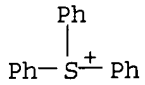
CMF C18 H15 S



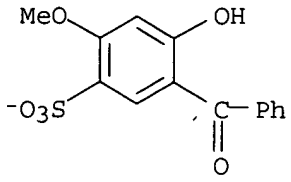
L19 ANSWER 17 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1991:644043 CAPLUS
DN 115:244043
TI Positive-working **photosensitive** composition
IN Aotani, Yoshimasa; Umehara, Akira; Yamaoka, Tsuguo
PA Fuji Photo Film Co., Ltd., Japan
SO Ger. Offen., 22 pp.
CODEN: GWXXBX
DT Patent
LA German
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4035425	A1	19910516	DE 1990-4035425	19901107
	DE 4035425	C2	19990527		
	JP 03154059	A2	19910702	JP 1989-294422	19891113
	US 5202216	A	19930413	US 1990-608801	19901105
PRAI	JP 1989-294422	A	19891113		

TI Positive-working **photosensitive** composition
ST **photosensitive** compn sensitivity contrast; onium salt sulfonic acid
IT Onium compounds
RL: USES (Uses)
(of sulfonic acids, **photosensitive** compns. containing)
IT Lithographic plates
(**photosensitive**, pos.-working, polymers and onium compound sulfonic acid salts in)
IT 137308-83-9P 137308-84-0P 137308-86-2P 137308-87-3P 137308-88-4P
137308-89-5P 137308-90-8P 137308-92-0P 137308-94-2P 137308-96-4P
137308-98-6P 137309-00-3P 137309-01-4P 137309-03-6P 137309-04-7P
137309-05-8P 137309-06-9P 137309-07-0P 137309-08-1P 137309-09-2P
137309-10-5P **137309-11-6P** 137309-12-7P 137309-13-8P
137309-14-9P 137309-15-0P 137309-16-1P 137309-17-2P 137309-18-3P
137309-20-7P 137309-22-9P 137309-23-0P 137309-25-2P 137309-26-3P
137309-27-4P 137309-28-5P 137309-29-6P 137309-30-9P 137309-33-2P
137309-34-3P 137309-35-4P 137309-36-5P 137309-37-6P 137309-38-7P
137309-39-8P 137309-40-1P 137337-63-4P 137337-64-5P 137337-66-7P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, in **photosensitive** composition)
IT **137309-11-6P**
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, in **photosensitive** composition)
RN 137309-11-6 CAPLUS
CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 65994-36-7
CMF C14 H11 O6 S



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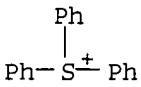
CMF C18 H15 S



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L3             STRUCTURE UPLOADED
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L5         51766 S L2 FULL
L6         83641 S L3 FULL
L7            40 S (L4 OR L5 OR L6) AND (SULFONIUM OR TRIPHENYLSULFONIUM)

     FILE 'CAPLUS' ENTERED AT 12:30:00 ON 25 JUL 2005
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L9           174 S PHENOL NOVOLAC
L10         2728 S PHENOL NOVOLAK
L11         7748 S PHENOLIC NOVOLAK
L12          147 S PHENOLIC NOVOLAC
L13            0 S L8 AND (L9 OR L10 OR L11 OR L12)
L14          381 S PHOTO THERMAL
L15            0 S L8 AND L14
L16        11801 S PRINTING PLATE
L17            2 S L8 AND L16
L18      2240033 S PHOTORESIST OR IMAGE OR PHOTOSENSITIVE OR THERMAL OR HEAT
L19           17 S L8 AND L18

=> d l17 1-2

L17  ANSWER 1 OF 2  CAPLUS  COPYRIGHT 2005 ACS on STN
AN   2004:633141  CAPLUS
DN   141:181996
TI   Image forming material
IN   Iwato, Kaoru
PA   Fuji Photo Film Co., Ltd., Japan
SO   U.S. Pat. Appl. Publ., 67 pp.
     CODEN: USXXCO
DT   Patent
LA   English
FAN.CNT 1
     PATENT NO.           KIND   DATE        APPLICATION NO.         DATE
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PI   US 2004152012         A1    20040805    US 2004-760497          20040121
     JP 2004226794         A2    20040812    JP 2003-15905           20030124
     JP 2004233854         A2    20040819    JP 2003-24499           20030131
PRAI JP 2003-15905         A     20030124
     JP 2003-24499         A     20030131
OS   MARPAT 141:181996

L17  ANSWER 2 OF 2  CAPLUS  COPYRIGHT 2005 ACS on STN
AN   2004:246983  CAPLUS
DN   140:294802
TI   Image forming material
IN   Iwato, Kaoru; Sorori, Tadahiro
PA   Fuji Photo Film Co., Ltd., Japan
SO   Eur. Pat. Appl., 94 pp.
     CODEN: EPXXDW
DT   Patent
LA   English
FAN.CNT 1
     PATENT NO.           KIND   DATE        APPLICATION NO.         DATE
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PI   EP 1400350           A2    20040324    EP 2003-20551           20030917
     EP 1400350           A3    20040414
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            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
    JP 2004109320        A2    20040408    JP 2002-269900         20020917
    JP 2004126049        A2    20040422    JP 2002-287818         20020930
    US 2004067435        A1    20040408    US 2003-662534         20030916
PRAI JP 2002-269900      A     20020917
    JP 2002-287818       A     20020930
OS  MARPAT 140:294802

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